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## Gluing Langmuir-Blodgett Monolayers onto Hydrocarbon Surfaces

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Organic thin films are of considerable current interest for a wide range of applications, including the fabrication of optical devices, sensors, transducers, protective coatings, permeation-selective barriers, patternable surfaces, and biomaterials.<sup>1,2</sup> Although the structure, composition and uniformity of the surface of such films play an important role in many of these applications, "brute-force" methods of surface modification (e.g., oxidation via corona discharge and plasma treatment) continue to be widely used.<sup>3</sup> Devising mild and efficient methods for introducing functional groups to hydrocarbon surfaces, with precise control over their density and distribution, remains as a major challenge.<sup>4,5</sup> Here, we describe one promising new approach that is based on the use of ionically cross-linked (i.e., "glued") monolayers.6 Specifically, we show how Langmuir-Blodgett (LB) monolayers that have been assembled from a multiply charged, calix[6]arene-based surfactant (1a) and glued together with poly(4-styrene sulfonate) (PSS, MW 30,000-50,000) form a stable coating on hydrocarbon surfaces with their polar headgroups extending outward into air (Chart 1).<sup>6,7</sup>

Chart 1



Consider a hydrophobic substrate that has been passed, vertically, down through a compressed monolayer of surfactant at an airwater interface. Normally, the substrate "picks up" the assembly and becomes hydrophilic while immersed in the subphase (Figure 1).<sup>7</sup> If the monolayer that remains at the air/water interface is then decompressed, and the substrate withdrawn into air, the surfactant is expected to return to the water surface; that is, such processes are normally reversible.<sup>8</sup> Now consider a hypothetical experiment, which uses a surfactant bearing multiple hydrocarbon chains and multiple ionic headgroups that have been ionically cross-linked by a polymeric counterion.<sup>6</sup> Here, increased interaction between the substrate and the monolayer, and increased cohesiveness within the thin film, due to multiple hydrocarbon contacts and ionic crosslinking, has the potential for preventing the return of the surfactant to the water surface. In principle, this could lead to a modified surface in which the polar headgroups extend outward into air (Figure 1).

To test this hypothesis, a monolayer of **1a** was spread on the surface of an aqueous subphase containing PSS (5 mM repeat unit concentration, 25 °C), and compressed to 30 dyn/cm at a rate of 25 cm<sup>2</sup>/min. A silicon wafer, which had been previously silylated



**Figure 1.** Stylized illustration. (Top): (1) Down-trip of a hydrophobic substrate through a compressed monolayer, picking up hypothetical surfactants, (2) decompression of the monolayer at the air/water interface, (3) removal of substrate into air, and return of surfactants to the water surface. (Bottom): Same as Top, except the surfactants bear multiple hydrocarbon chains and multiply charged headgroups, which are ionically cross-linked, resulting in retention on the substrate.

with n-octadecyltrichlorosilane (OTS), was then immediately passed, vertically, down through the monolayer at a speed of 2 mm/min. The transfer ratio was  $1.0 \pm 0.1$ . After allowing the substrate to remain submerged for 60 min, the residual monolayer at the air/ water interface was decompressed to 0 dyn/cm and the substrate removed, vertically, from the subphase. None of the surfactant returned to the water surface, as evidenced by the fact that recompression of the film to 30 dyn/cm showed the same occupied area as that found after the down-trip. After rinsing substrate with pure water, examination by atomic force microscopy (AFM) revealed a surface that was uniform on a micrometer-scale (Figure 2). The advancing contact angle for water was  $46^{\circ} \pm 2^{\circ}$ . Exposure to the laboratory ambient for an additional 48 and 120 h resulted in contact angles of  $49^{\circ} \pm 1^{\circ}$  and  $51^{\circ} \pm 1^{\circ}$ , respectively. Retention of surface hydrophilicity was also evident after six repetitive washing cycles with pure water, where a contact angle of  $51^{\circ} \pm$ 2° was observed (the same value was observed after three washing cycles). The contact angle for water on the OTS-modified silicon wafer, itself, was  $108^\circ \pm 2^\circ$ . The ellipsometric thickness of this glued monolayer (2.6  $\pm$  0.03 nm) was comparable to half the thickness of glued and unglued LB bilayers of 1a, which were 2.82 and 2.4 nm, respectively.<sup>6</sup> Further examination by X-ray photoelectron spectroscopy (XPS) revealed a S/N atomic ratio of ca. 1.3, which was independent of the "take off" angle used, from 11.5 to 53.1° (Figure 3). Also, an enrichment of both of these elements at the outer surface of the film was clearly evident.

A similar surface modification was performed with an OTSmodified silicon wafer, except that the monolayer of **1a** was transferred after first being incubated over the PSS subphase for 60 min at 30 dyn/cm. In separate experiments, we have found that the surface viscosity of such monolayers increases to a maximum during this time. In this case, the down-trip resulted in a transfer ratio of  $0.7 \pm 0.1$ , indicating a less-than-perfect transfer. On the up-trip, none of the surfactant was returned to the water surface. Examination of this substrate by AFM showed the presence of defects, and a "peak-to-valley" distance of ca. 3 nm, which is consistent with ellipsometry measurements for such film (Figure



**Figure 2.** Height image and section profiles (AFM, tapping mode, 1  $\mu$ m × 1  $\mu$ m) of a deposited monolayer of **1a** on an OTS-modified silicon wafer using: (Top) an aqueous subphase containing 5 mM PSS; (Middle) same as Top, except that the monolayer was held for 60 min at 30 dyn/cm prior to transfer; (Bottom) a pure water subphase was used. All transfers were made using a speed of 2 mm/min and a surface pressure of 30 dyn/cm. Monolayers that were deposited from a PSS subphase were washed with water (three times, 10 min per rinse); the monolayer shown here, which was deposited from a pure water subphase, was examined without washing.



**Figure 3.** Atomic ratios of N/C (×100) for glued ( $\blacksquare$ ) and unglued ( $\square$ ) monolayers of **1a**, as well as S/N atomic ratios for glued monolayers ( $\bullet$ ) determined by angle-resolved XPS. Monolayers were transferred to OTS-modified silicon substrates using a transfer speed of 2 mm/min and a surface pressure 30 dyn/cm. Here,  $\Theta$  is the takeoff angle for XPS data collection. Prior to XPS analysis, the glued monolayer was washed with water (three times, 10 min per rinse); the nonglued monolayer was analyzed without rinsing.

2). A similar transfer of a monolayer of **1a** that was carried out in the absence of PSS showed a transfer ratio of 1.0  $\pm$  0.1 and no return of the surfactant to the water surface on the up-trip. Before being rinsed with water, this surface was found to be rich in defects (Figure 2). The presence of such defects, together with a "peakto-valley" distance of ca. 6 nm implies that the assembly has undergone rearrangement to bilayers. Examination by XPS, using various takeoff angles, showed a nitrogen content that was greater beneath the surface of the film (Figure 3). This result lends further support for a bilayer structure. Upon rinsing with water, 1a was completely removed from this surface, as evidenced by a combination of ellipsometry and AFM measurements. Taken together, these results indicate that six alkyl chains per surfactant are sufficient to maintain contact with the OTS-modified silicon wafer during the up-trip, but that ionic cross-linking is essential for producing a stable assembly, which can retain its structure and orientation in air.

Control experiments that were carried out using a conventional double-chain surfactant (2), bearing one quaternary ammonium group, resulted in a transfer ratio of  $1.0 \pm 0.1$  on the down-trip into aqueous PSS. On the up-trip, however, all of the surfactant



*Figure 4.* Plot of ellipsometric film thickness versus number of layers of polymeric counterions deposited onto a silylated silicon wafer that was modified with 1a/PSS. Here,  $P^-$  is PSS and  $P^+$  is PDADMA.

was returned to the air-water interface. When a polymeric surfactant [poly(octadecylmaleic anhydride), **POM**] was transferred to an OTS-modified silicon wafer, the transfer ratio on the down-trip was  $1.0 \pm 0.1$ , and none of the surfactant was returned to the water surface on the up-trip. However, examination by AFM revealed a film that was rich in defects and a peak-to-valley distance of ca. 4.6 nm, implying that the assembly had undergone rearrangement, most probably to a bilayer structure (Supporting Information). Attempted use of **1b**, bearing four alkyl chains and four quaternary ammonium groups resulted in a transfer ratio of  $1.0 \pm 0.1$  for the down-trip, but a significant return of the surfactant (ca. 30-50%) to the surface on the up-trip, in the absence and in the presence of PSS. Apparently, more than four alkyl chains and four quaternary ammonium groups are necessary to produce a stable coating.

In preliminary studies, we have found that glued monolayers of **1a** on OTS-modified silicon wafers, can be used to anchor alternating layers of PDADMA and PSS ions by conventional layerby-layer dipping.<sup>9,10</sup> Figure 4 shows the observed ellipsometric film thickness as a function of number of deposited layers. These thickness values, and the advancing contact angle for water of 55° for the final deposited layer of PSS are in good agreement with previous literature reports using hydrophilic substrates.<sup>11</sup>

Studies that are currently in progress are being aimed at defining the full scope of this technique with a view toward the development of ultrathin, permeation-selective barriers.

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**Supporting Information Available:** Synthesis of **1b**, silylation, LB and layer-by-layer deposition, surface viscosity data, and AFM scans. This material is available free of charge via the Internet at http:// pubs.acs.org.

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